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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Sato, et al.
Int'l Appl. No.	:	PCT/JP2003/016266
Int'l Filing Date	:	December 18, 2003
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Unknown
Group Art Unit	:	Unknown

PRELIMINARY AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination on the merits, please amend the present application.

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.